

SMALL-SCALE INSTALLATION FOR FILM DEPOSITION BY THERMAL EVAPORATION

MVU TM TIS 01

Purpose:

Film deposition by thermal evaporation.

Special characteristics:

- Substrate processing in one technological cycle (single-sided processing):
Ø 100 mm – 4 pcs.
- Microprocessing control system;
- Periodical quarter-turn of substrate holder;
- Oil-free pumping system (turbomolecular pump 60 l/h);
- Consumed power not more than 4,5 kW;
- 2,5 m² area per one installation.

